IAP4 Rec'd PCT/PTO 12 JAN 2006

NATIONAL PHASE UTILITY APPLICATION

Transmittal to the (DO/EO/US)
Under 35 USC 371

Attorney Docket No.: SHIGA7.036APC
First Named Inventor: Yasuo Masuda
Int'l Application No.: PCT/JP2004/010270

Int'l Filing Date: July 13, 2004 Priority Date Claimed: July 16, 2003

Title: POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN

Express Mail Label No.: EV718232865US

Direct all correspondence to Customer No.: 20995

Date: January 12, 2006

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The following enclosures are transmitted herewith to be filed in the patent application of:

Inventors:

1. Yasuo Masuda

2. Toshiki Okui

APPLICATION ELEMENTS:

- (X) This is a FIRST submission of items concerning a filing under 35 U.S.C. § 371.
- (X) A copy of the International Application as filed (35 U.S.C. § 371(c)(2)) has been communicated by the International Bureau.
 - (X) PCT/IB/308 enclosed.
- (X) An English translation of the International Application as filed is attached hereto.
- (X) Amendments to the claims of the International Application under PCT Article 19 (35 U.S.C. § 371(c)(3)) have not been and will not be made.
- (X) An Oath or Declaration signed by the inventors (35 U.S.C. § 371(c)(4)).

OTHER APPLICATION PARTS:

- (X) Preliminary Amendment in 5 pages.
- (X) Recordation form cover sheet and Assignment in 3 total pages (cover sheet & assignment).
- (X) An Information Disclosure Statement and PTO/SB/08 equivalent listing references for consideration:
 - (X) Listing 15 references.
 - (X) Enclosing 10 references.
- (X) Cover page of PCT publication WO 2005/007719 A3.
- (X) International Search Report and Written Opinion.
- (X) Application Data Sheet in 2 pages.

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(X) Return prepaid postcard.

FILING FEES:

		FEE CALCULA	TION				
FEE TYPE & DETERMINATION			LARGE FEE	CALCULATION			TOTAL
Basic Filing Fee under 1.492(a)			1631 (\$300)				\$300
Search Fee under 1.492(b) (enter one in TOTAL column)							
(1)	USPTO was ISA/(1640 (\$0)					
(2)	USPTO was the ISA (noncompliant claims)		1641 (\$100)				\$400
(3)	Foreign Search Re	1642 (\$400)					
(4)	No Search Report	Enclosed	1632 (\$500)	1			İ
Examination Fee under 1.492(c) (enter one in TOTAL column)							
(1) U	SPTO was ISA/IPEA	1643 (\$0)	1			\$200	
(2) Non US IPEA or Noncompliant Claims			1633 (\$200)	1			
Exces	ss Claims	5 - 20 = 0	1615 (\$50)	0	x	50 =	\$0
Excess Ind. Claims		1 - 3 = 0	1614 (\$200)	0	х	200 =	\$0
Multiple Dep. Claim			1616 (\$360)				\$0
Application Size Fee		0 - 100 = 0	1681 (\$250)	0	x	250 =	\$0
Late English Translation		1618 (\$130)					
Assignment			8021 (\$40)	1	х	40 =	\$40
TOTAL FEE DUE							\$940
TOTAL FEE PAID (If Different Than Fee Due)							s

(X) A check in the amount of \$940 to cover the Total Fee Due is enclosed.

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The Commissioner is hereby authorized to charge any additional fees which may be required, now or in the future, or credit any overpayment to Account No. 11-1410.

Daniel E. Altman Registration No. 34,115 Attorney of Record Customer No. 20,995 (949) 760-0404

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